

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("20020025495").PN.	US-PGPUB; USPAT	OR	OFF	2007/03/22 13:19
S3	237	430/270.1.ccls. and \$silsesquiox\$	US-PGPUB; USPAT	OR	OFF	2007/03/22 13:20
S4	157	430/270.1.ccls. and \$silsesquiox\$ and (photoacid or photo adj acid)	US-PGPUB; USPAT	OR	OFF	2007/03/22 13:20
S5	141	430/270.1.ccls. and \$silsesquiox\$ and (photoacid or photo adj acid) and positiv\$	US-PGPUB; USPAT	OR	ON	2007/03/22 13:24
S6	5	\$silsesquiox\$ and (photoacid or photo adj acid) and positiv\$	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 13:25
S7	289	\$silsesquiox\$ and (photoacid or photo adj acid) and positiv\$	US-PGPUB; USPAT	OR	ON	2007/03/22 14:52
S8	148	S7 not S5	US-PGPUB; USPAT	OR	ON	2007/03/22 13:25
S9	1	2003-112005.NRAN.	DERWENT	OR	OFF	2007/03/22 13:27
S10	86	\$silsesquiox\$ and (photoacid or photo adj acid) and positiv\$ and magnetic	US-PGPUB; USPAT	OR	ON	2007/03/22 14:34
S11	80	\$silsesquiox\$ and (photoacid or photo adj acid) and positiv\$ and magnetic and (etch etches etched etching)	US-PGPUB; USPAT	OR	ON	2007/03/22 14:34
S12	58	magnetic same (etch etched etches etching) and (photoacid or photo adj acid) and positiv\$	US-PGPUB; USPAT	OR	ON	2007/03/22 15:01
S13	32	magnetic same (etch etched etches etching) and bilayer adj resist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 15:02

S14	2	magnetic adj film same (etch etched etches etching) and bilayer adj resist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 15:05
S15	1	magnetic adj film same (etch etched etches etching) same "metallic oxidation prevention"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 15:07
S16	1	magnetic adj film same (etch etched etches etching) same "oxidation prevention"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 15:06
S17	38	magnetic adj film same (etch etched etches etching) same ("tantalum" or aluminum adj oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 15:07
S18	26	magnetic adj film same (etch etched etches etching) same ("tantalum" or aluminum adj oxide) and photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/22 15:08
S19	5	("20020025495" "20030219676" "5399462" "5612170" "5691396").PN.	US-PGPUB; USPAT	OR	OFF	2008/10/20 18:44
S20	2	("20020025495").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/10/22 16:08
S22	2	JP-08334900-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 16:12
S23	2	JP-08334901-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 16:40
S24	1	1997-096817.NRAN.	DERWENT	OR	OFF	2008/10/22 16:40
S25	0	("57131126").PN.	US-PGPUB; USPAT	OR	OFF	2008/10/22 16:42
S26	1	("5731126").PN.	US-PGPUB; USPAT	OR	OFF	2008/10/22 16:42

S27	8	("4600685" I "4657843" I "4722881" I "4822716" I "4981778" I "5057396" I "5338818" I "5547808"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/10/22 16:42
S28	16	("5731126").URPN.	USPAT	OR	OFF	2008/10/22 17:01
S29	2	JP-63101427-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:32
S30	2	JP-63090534-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:33
S31	2	JP-08029987-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:49
S32	2	JP-08160620-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:50
S33	2	JP-09087391-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:50
S34	2	JP-2002055452-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:51
S35	2	JP-2001265006-S.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/22 17:57
S36	208	ofpr800	US-PGPUB; USPAT	OR	OFF	2008/10/23 15:31
S37	2614	(acetal ketal) same3 (alicyclic cylohexyl)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/10/23 15:42

S38	3276	(acetal ketal) same3 (alicyclic cyclohexyl)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/23 15:42
S39	3287	(acetal ketal) same3 (alicyclic Scylcohexyl\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/23 15:42
S40	1464	(acetal ketal) same3 (alicyclic Scylcohexyl\$) and (PHOTOCLEAV\$ CLEAV\$ DEGRADS DECROSSLINKS LABILE cleft PHOTOLABILE LYSABLE PHOTOLYSABLE ACID- LYSIBLE dissocia\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/23 15:43
S41	617	(acetal ketal) same (alicyclic Scylcohexyl\$) and (PHOTOCLEAV\$ CLEAV\$ DEGRADS DECROSSLINKS LABILE cleft PHOTOLABILE LYSABLE PHOTOLYSABLE ACID- LYSIBLE dissocia\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/23 15:45
S42	399	(acetal ketal) same (alicyclic Scylcohexyl\$) and (PHOTOCLEAV\$ CLEAV\$ DEGRADS DECROSSLINKS LABILE cleft PHOTOLABILE LYSABLE PHOTOLYSABLE ACID- LYSIBLE dissocia\$) and (positiv\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/23 15:45
S43	184	(acetal ketal) with (alicyclic Scylcohexyl\$) and (PHOTOCLEAV\$ CLEAV \$ DEGRADS DECROSSLINKS LABILE cleft PHOTOLABILE LYSABLE PHOTOLYSABLE ACID- LYSIBLE dissocia\$) and (positiv\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/10/23 15:50
S44	1	("4701508").PN.	US-PGPUB; USPAT	OR	OFF	2008/10/23 16:08

S45	2	("20020081520").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF ²	2008/10/23 16:29
S46	2	("20020090572").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF ²	2008/10/23 16:32
S47	2	("20020113241").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/10/23 16:33
S48	2	("20030139486").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF ²	2008/10/23 16:34
S49	2	("20030224291").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF ²	2008/10/23 16:36
S50	2	("20040209187").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF ²	2008/10/23 18:05

10/27/08 12:15:28 PM

C:\Documents and Settings\CHamilton\My Documents\EAST\Workspaces\10560126.wsp